Transfer-free chemical vapor deposition of graphene on silicon substrate at atmospheric pressure: A sacrificial catalyst

Samira Naghdi, Kyong Yop Rhee, Soo Jin Park

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Transfer-free chemical vapor deposition of graphene on silicon substrate at atmospheric pressure: A sacrificial catalyst

Samira Naghdi[1], Kyong Yop Rhee[1,*], Soo Jin Park [2,**]

[1]Department of Mechanical Engineering, College of Engineering, Kyung Hee University, 446-701, Yongin, Korea

[2]Department of Chemistry, College of Natural Science, Inha University, 402-751, Incheon, Korea

*Corresponding author. Tel: +82 31 201 2565, Fax: +82 31 202 6693, rheeky@khu.ac.kr (K. Rhee)

**Co-corresponding author. Tel: +82 32 876 7234, Fax: +82 32 860 8438, sjpark@inha.ac.kr (S. J. Park)